

Form 1449 (Modified)

Information Disclosure
Statement By Applicant

(Use Several Sheets if Necessary)

Atty Docket No.

LAM1P124D1

Application No.:

Not Yet Assigned

Applicant

Bailey III et al.

Filing Date

Herewith

Art Group Unit

Unknown

Page 1 of 1

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 08/30/01

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A.	4,690,793	09/1987	"Hitachi, Ltd. et al."			
	B.	4,948,458	08/1990	Ogle			
	C.	4,990,229	02/1991	Campbell et al.			
	D.	5,091,049	02/1992	Campbell et al.			
	E.	5,122,251	06/1992	Campbell et al.			
	F.	5,242,264	09/1993	Kojima et al.			
	G.	5,356,661	10/1994	Doi et al.			
	H.	5,421,891	06/1995	Campbell et al.			
	I.	5,429,070	07/1995	Campbell et al.			
	J.	5,587,038	12/1996	Cecchi et al.			
	K.	5,788,799	08/1998	Steger et al.			
	L.	5,885,356	03/1999	Zhao et al.			
	M.	6,063,199	05/2000	Sajoto et al.			
	N.	6,165,271	12/2000	Zhao et al.			

Foreign Patent or Published Foreign Patent Application

Examiner Initial		Document No.	Publication Date	Country or Patent Office	Class	Sub-Class	Translation	
							Yes	No
	O.	0 819 780 A2	01/1998	EPO				
	P.	0 837 489 A2	04/1998	EPO				
	Q.	0 838 842 A2	04/1998	EPO				
	R.	0 838 843 A2	04/1998	EPO				
	S.	JP61-104291	05/1986	Japan				

Other Documents

Examiner Initial	No.	Author, Title, Place (e.g. Journal) of Publication, Date
	T.	Y. Fujiwara et al., "Temperature control of plasma grid for continuous operation in cesium-seeded volume negative ion source," Rev. Sci. Inst. 69 (2), 2.98, pp. 1173-1175.
	U.	Mizuhara et al., "Ceramic/Metal Seals," Engineering Materials Handbook, 11.95, pp. 502-210.
	V.	D.R. Write et al., "Low temperature etch chuck: Modeling and experimental results of heat transfer and wafer temperature," J. Vac. Sci. Technol. A 10 (4), 7.92, pp. 1065-1070.
Examiner		Date Considered 04/03/02

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered.
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DEC 12 2001

Attorney Docket No.

LAM1P124D1

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BAILEY III et al.

Filing Date

08/30/2001

Group

1763

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
<i>LD</i>	A.	5,707,452	01/1998	Dandl			
	B.	5,795,451	08/1998	Tan et al.			
	C.	6,113,731	09/2000	Shan et al.			
	D.	6,178,920	01/2001	Ye et al.			
	E.	6,196,155	03/2001	Setoyama et al.			
	F.						

Foreign Patent or Published Foreign Patent Application

Examiner Initial	Document No.	Publication Date	Country or Patent Office	Class	Sub-Class	Translation Yes	Translation No
	G.						
	H.						
	I.						

Other Documents

Examiner Initial	No.	Author, Title, Place (e.g. Journal) of Publication, Date
	J.	
	K.	
	L.	
	M.	
	N.	
	O.	
	P.	
	Q.	
Examiner <i>Alexander</i>		Date Considered <i>01/03/02</i>

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